

# Ultraviolet semiconductor diode lasers for novel applications

## Sandia National Laboratories

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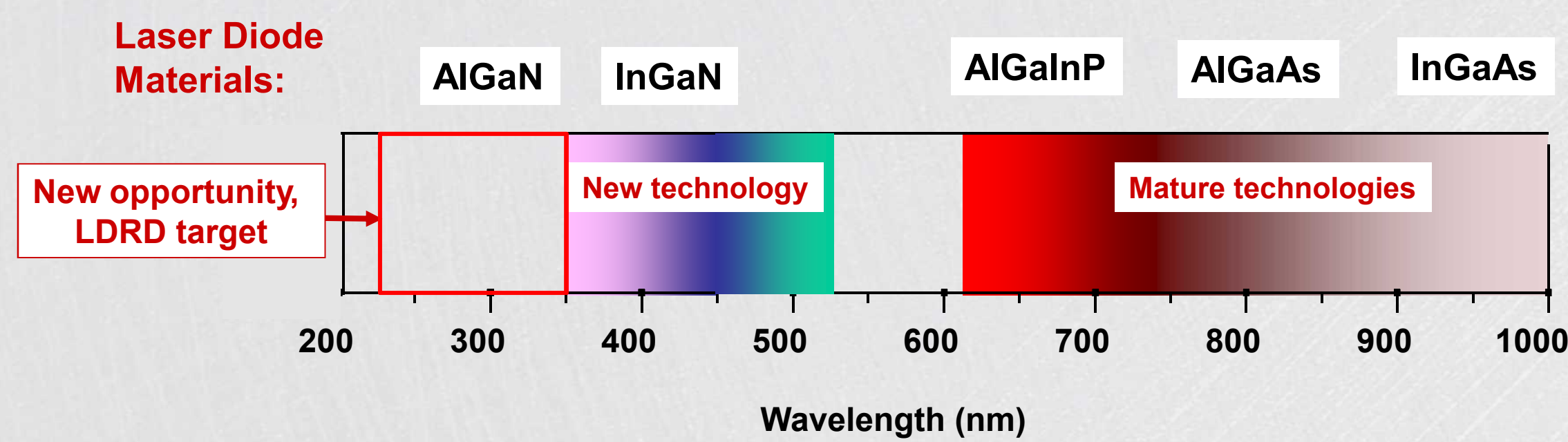
LABORATORY DIRECTED RESEARCH & DEVELOPMENT

## Nuclear Weapons EAB Review

### Problem

#### Opportunity:

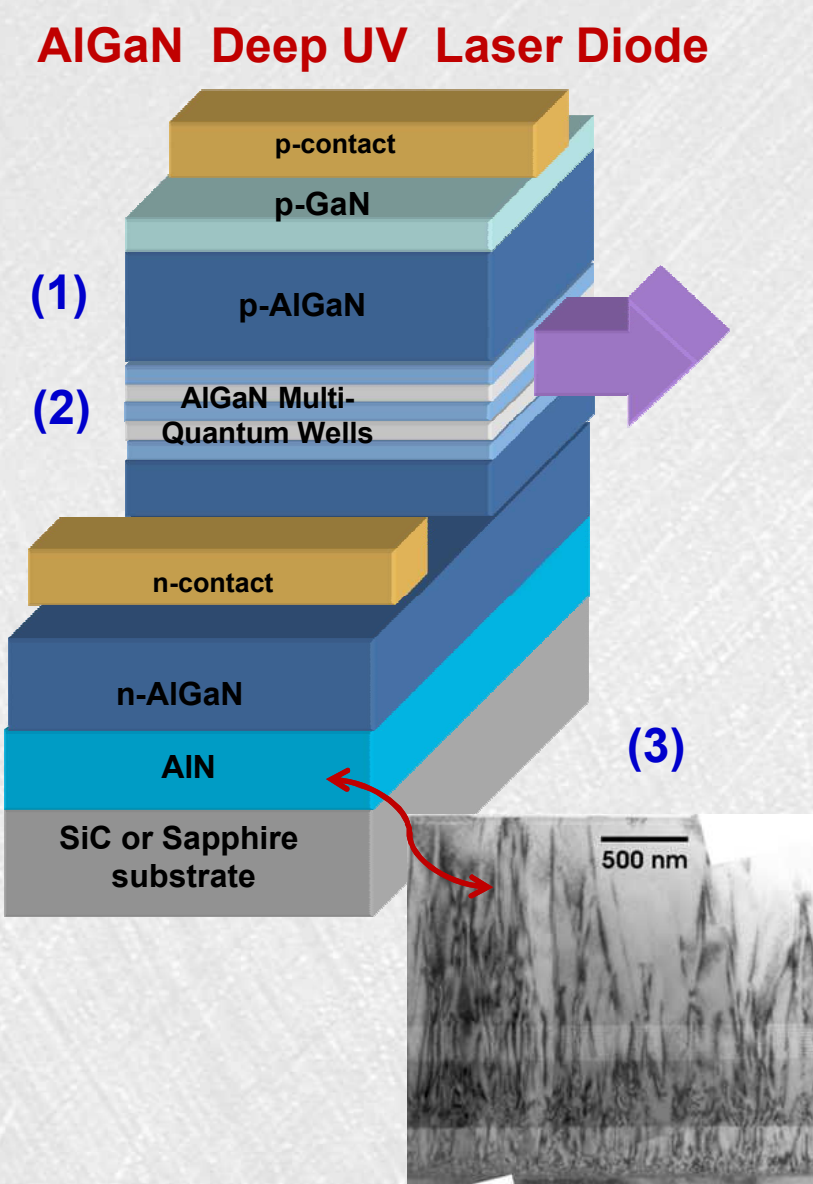
- A number of mission-critical applications would greatly benefit from extending semiconductor laser diode technology to deep UV wavelengths ( $\leq 340$  nm)
- AlGaIn semiconductor alloys are emerging as the most promising candidate materials to enable a compact, high-performance mid-to-deep UV laser source



#### Problem:

- AlGaIn semiconductors present several **major materials roadblocks** to laser demonstration:

- (1) Ineffective p-type doping of AlGaIn epilayers  
→ large ( $> 200$  meV) acceptor ionization energies
- (2) Non-radiative point defects (vacancies, impurities)  
→ reduces efficiency, impacted by growth conditions
- (3) Lack of a lattice-matched substrate  
→ high threading dislocation density  $> 1 \times 10^9$  cm $^{-2}$ ; reduces efficiency, reliability



### Approach

Explore innovative, science-based approaches to overcoming major AlGaIn roadblocks

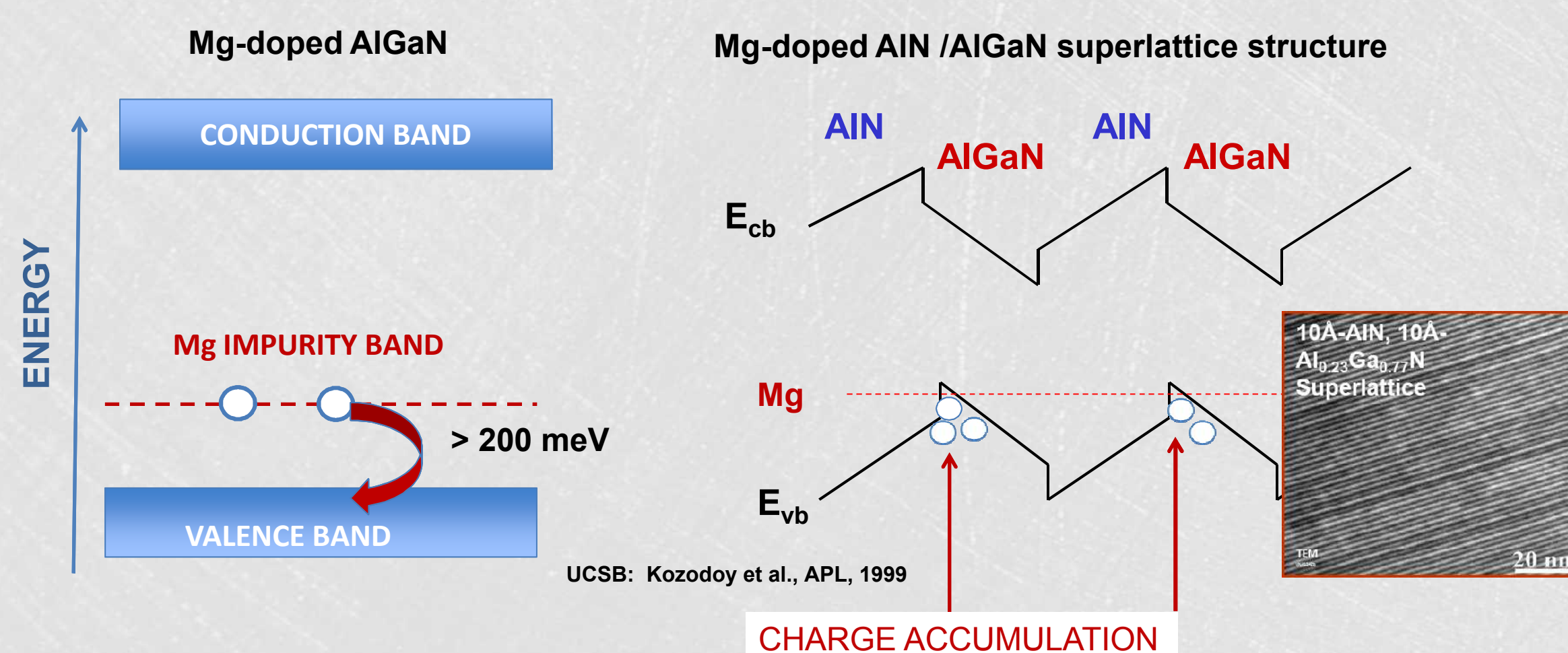
#### Enabling Capabilities:

- State-of-the-Art MESA facility for:
- Epitaxial materials growth
  - Device processing
  - Materials and device characterization



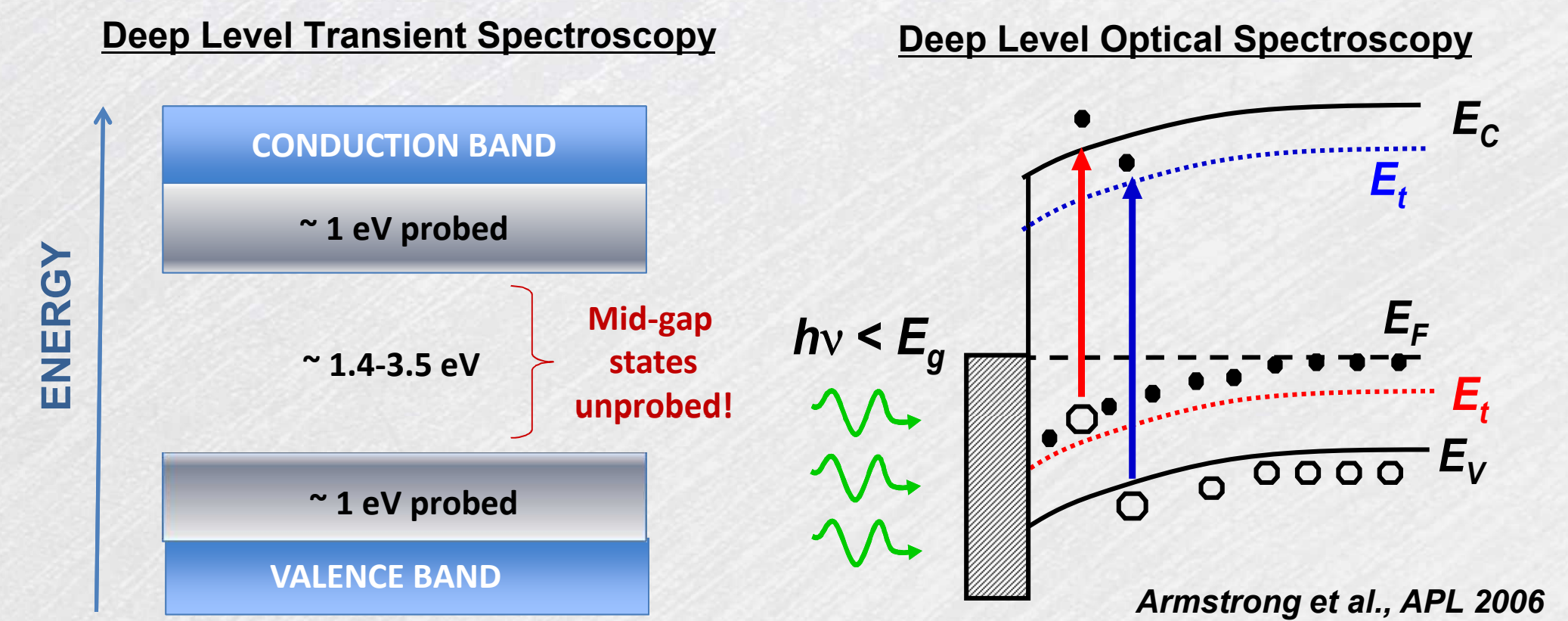
Metal-organic vapor-phase epitaxy system for growth of AlGaIn alloys and device structures

#### (1) AlGaIn/AlN Mg-doped superlattices for improved hole injection



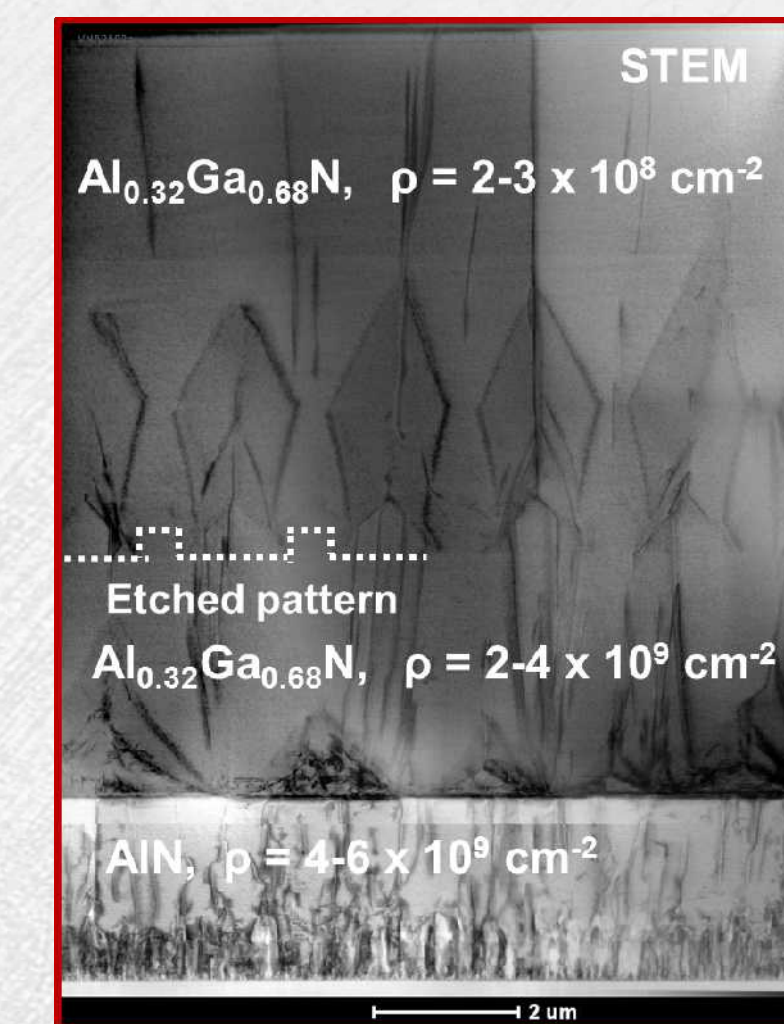
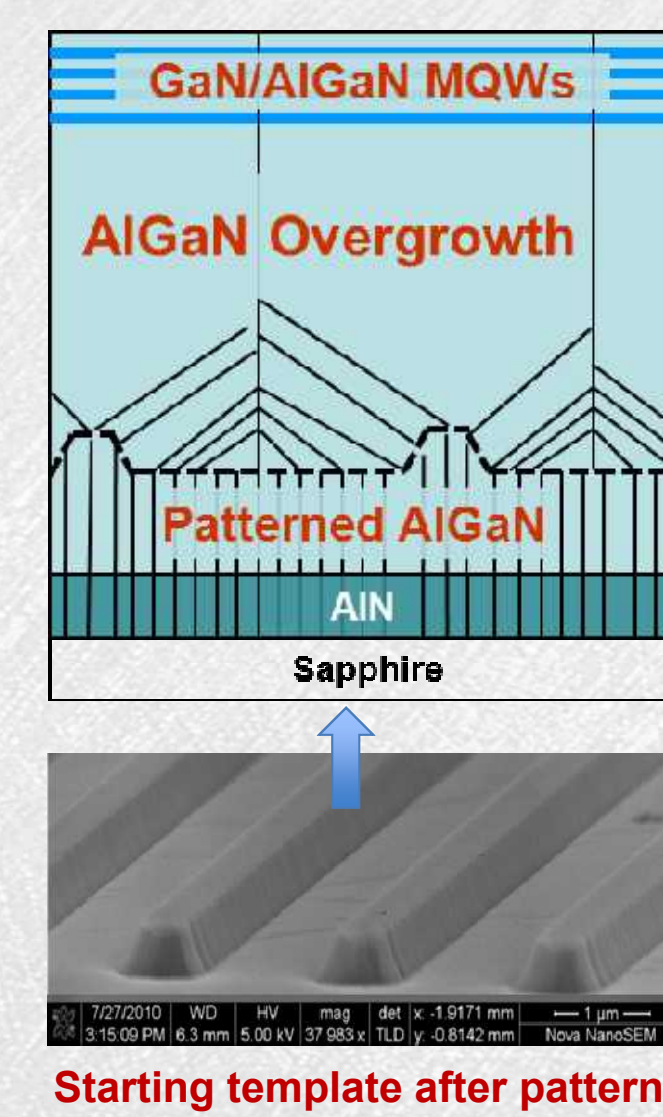
- Mg acceptor level is  $> 200$  meV above the valence band. Thermal activation of holes at room temperature ( $kT \sim 26$  meV) is ineffective
- Internal polarization fields in AlGaIn/AlN multilayer structure modify band profiles and lead to enhanced acceptor ionization and hole accumulation

#### (2) Deep Level Optical Spectroscopy (DLOS) to quantify and mitigate point defects



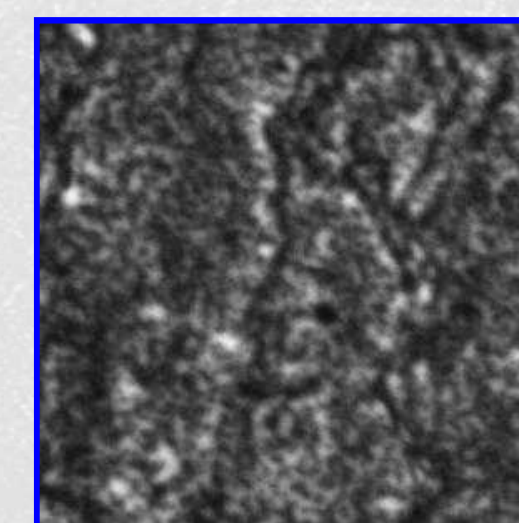
- DLOS technique employs *optical ionization* of defect levels to probe defects throughout the bandgap, including mid-gap non-radiative centers
- Anticipate *unprecedented quantitative information* on defect properties and their correlation with growth conditions and radiative efficiency/optical gain

#### (3) Patterned regrowth strategies to mitigate extended defects

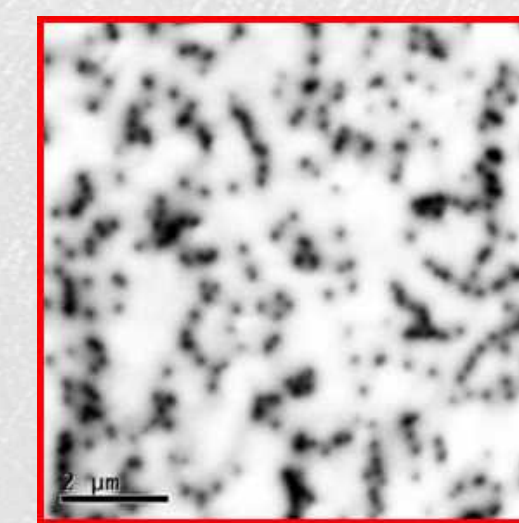


Overgrowth of etched trenches  
Strain induced 3D islanding

#### Cathodoluminescence of AlGaIn quantum wells (top view of wafers)

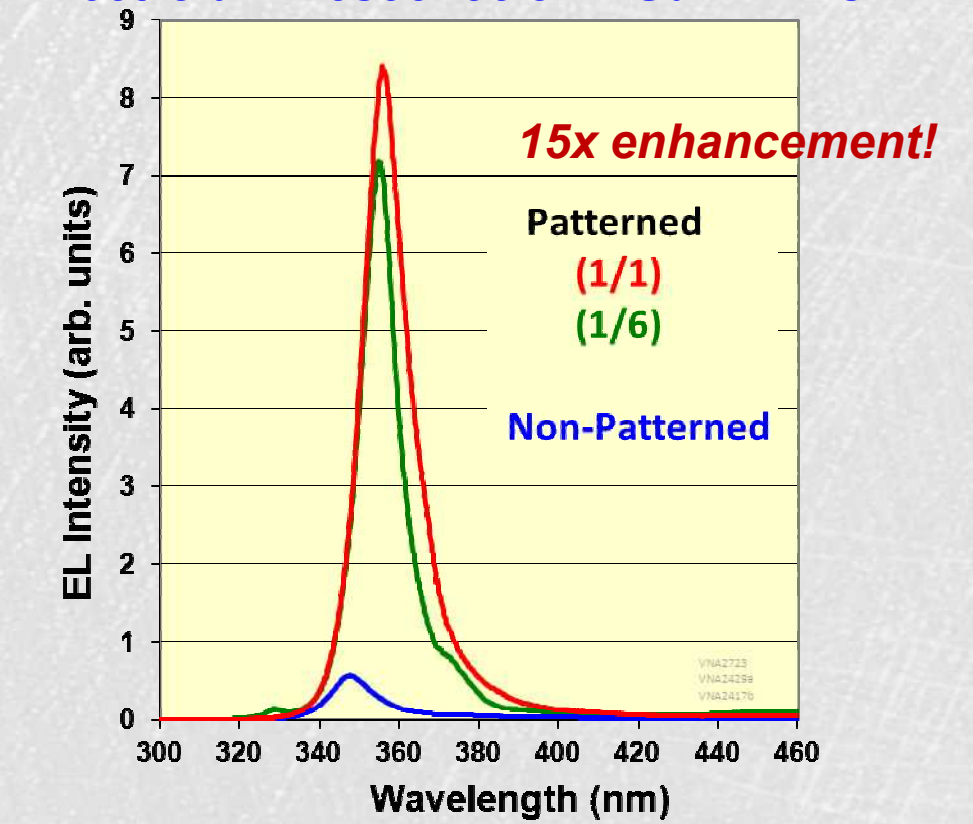


Al<sub>0.30</sub>Ga<sub>0.70</sub>N No patterning



Al<sub>0.30</sub>Ga<sub>0.70</sub>N Patterned growth

#### Electroluminescence of AlGaIn LEDs



- Advance *innovative approaches* to reduce threading dislocations for high luminescence efficiency and optical gain
- New work will focus on more challenging alloys and strategies for greater defect reduction

### Significance

- Success would be a **major technological breakthrough**, achieving the shortest wavelength laser diodes to date with custom properties for NW applications
- Enables entirely new approaches for numerous other applications including fluorescence-based biosensing, trapped-ion quantum computing, water and air purification.

